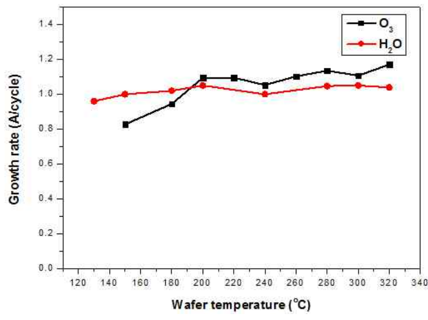

Figure 1. Thermal ALD windows of the new precursor with H_2O or O_3.

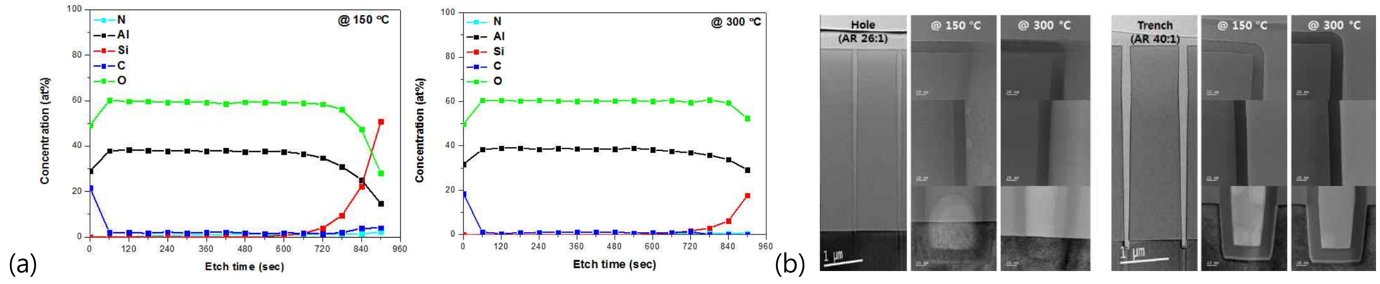

Figure 2. (a) XPS data and (b) TEM images of the Al_2O_3 deposited at 150 and 300 °C using the new precursor and H_2O.